David M Hoffman

List of Publications by Year
in descending order

45 papers	2,166 citations	236925 25 h-index	254184 43 g-index
45 all docs	45 docs citations	45 times ranked	1384 citing authors

#	Article	IF	Citations
1	Perpendicular and parallel acetylene complexes. Journal of the American Chemical Society, 1982, 104, 3858-3875.	13.7	227
2	Chemical vapor deposition of titanium, zirconium, and hafnium nitride thin films. Chemistry of Materials, 1991, 3, 1138-1148.	6.7	210
3	Synthesis of thin films by atmospheric pressure chemical vapor deposition using amido and imido titanium(IV) compounds as precursors. Chemistry of Materials, 1990, 2, 235-241.	6.7	192
4	Chemical vapor deposition of vanadium, niobium, and tantalum nitride thin films. Chemistry of Materials, 1993, 5, 614-619.	6.7	165
5	Chemical vapour deposition of nitride thin films. Polyhedron, 1994, 13, 1169-1179.	2.2	148
6	Isoelectronic molecules with triple bonds to metal atoms (M = Mo, W): crystal and molecular structures of tri-tert-butoxytungsten ethylidyne and nitride. Inorganic Chemistry, 1983, 22, 2903-2906.	4.0	100
7	Metal alkoxides: models for metal oxides. 4. Alkyne adducts of ditungsten hexaalkoxides and evidence for an equilibrium between dimetallatetrahedrane and methylidynemetal complexes: W2(.mu.-C2H2) .dblharw. 2W.tplbond.CH. Journal of the American Chemical Society, 1984, 106, 6794-6805.	13.7	95
8	Synthesis of Homoleptic Gallium Alkoxide Complexes and the Chemical Vapor Deposition of Gallium Oxide Films. Chemistry of Materials, 2001, 13, 2135-2143.	6.7	88
9	Solution-phase reactivity as a guide to the low-temperature chemical vapor deposition of early-transition-metal nitride thin films. Journal of the American Chemical Society, 1990, 112, 7833-7835.	13.7	83
10	General Synthesis of Homoleptic Indium Alkoxide Complexes and the Chemical Vapor Deposition of Indium Oxide Films. Journal of the American Chemical Society, 2000, 122, 9396-9404.	13.7	56
11	Metal alkoxides models for metal oxides. 5. Coupling of alkyne ligands in reactions involving ditungsten hexaalkoxides: an alternative to the metathesis reaction M.tplbond.M + C.tplbond.C- .fwdarw. 2M.tplbond.C. Journal of the American Chemical Society, 1984, 106, 6806-6815.	13.7	53
12	Low-temperature atmospheric pressure chemical vapor deposition of polycrystalline tin nitride thin films. Chemistry of Materials, 1992, 4, 68-71.	6.7	53
13	Synthesis of aluminium and gallium fluoroalkoxide compounds and the low pressure metal-organic chemical vapor deposition of gallium oxide films. Journal of Materials Chemistry, 1999, 9, 929-935.	6.7	53
14	Synthesis of Tin Oxide Precursors and Related Germanium and Lead Compounds. Inorganic Chemistry, 1996, 35, 6164-6169.	4.0	47
15	Atmospheric pressure chemical vapor deposition of aluminum nitride thin films at 200â€“250 Â°C. Journal of Materials Research, 1991, 6, 5-7.	2.6	41
16	Chemical vapor deposition of aluminum nitride thin films. Journal of Materials Research, 1992, 7, 1679-1684.	2.6	41
17	Atmospheric-pressure chemical vapor deposition of fluorine-doped tin oxide thin films. Thin Solid Films, 1999, 345, 240-243.	1.8	40
18	Indium Fluoroalkoxide Compounds. Inorganic Chemistry, 1999, 38, 4447-4454.	4.0	37

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19	Metal alkoxides: models for metal oxides. 7. Trinuclear and tetranuclear alkylidyne clusters of tungsten supported by alkoxide ligands. Journal of the American Chemical Society, 1985, 107, 1234-1241.	13.7	36
20	Reactions involving alkynes and tungsten-tungsten triple bonds supported by alkoxide ligands. Polyhedron, 1987, 6, 783-792.	2.2	35
21	Low-temperature atmospheric-pressure metal-organic chemical vapor deposition of molybdenum nitride thin films. Thin Solid Films, 1996, 288, 116-119.	1.8	35
22	Synthesis of Indium Amide Compounds. Inorganic Chemistry, 1998, 37, 3835-3841.	4.0	34
23	Silicon dimethylamido complexes and ammonia as precursors for the atmospheric pressure chemical vapor deposition of silicon nitride thin films. Chemistry of Materials, 1990, 2, 480-482.	6.7	33
24	Titanium Nitride Thin Films: Properties and Apcvd Synthesis Using Organometallic Precursors. Materials Research Society Symposia Proceedings, 1989, 168, 357.	0.1	31
25	Low temperature chemical vapor deposition of titanium nitride films from tetrakis(ethylmethylamido)titanium and ammonia. Thin Solid Films, 1999, 357, 125-131.	1.8	25
26	Indium Tris(alkylthiolate) Compounds. Inorganic Chemistry, 1998, 37, 5823-5826.	4.0	23
27	[Ni(PtBu)6] and[Ni(SiH2)6] Are Isolobal, Related to[In{Mn(CO)4}5]2â^', and Have 16-Electron Counts. Angewandte Chemie International Edition in English, 1993, 32, 1616-1618.	4.4	22
28	Synthesis and Structural Characterization of Tantalum(IV) Amido Compounds. Inorganic Chemistry, 1996, 35, 5015-5018.	4.0	22
29	Low pressure chemical vapor deposition of fluorine-doped indium oxide films from an indium alkoxide complex. Journal of Materials Chemistry, 2000, 10, 2392-2395.	6.7	22
30	Synthesis of Copper(I) Complexes with Ketimide and Hydrazide Ligands. Journal of Cluster Science, 2010, 21, 567-575.	3.3	20
31	Further studies of the reactions involving ethyne and M2(OBut)6, where M î—» Mo and W. Polyacetylene formation versus formation of ethyne adducts and Cî—¸C coupled products. Polyhedron, 1997, 16, 839-847.	2.2	13
32	Organometallchemie mit MolybdÃnâ€•und Wolframalkoxidclustern; Vergleich mit Carbonylclustern der spÄten Ãœbergangsmetalle. Angewandte Chemie, 1989, 101, 446-458.	2.0	12
33	Synthesis and structures of Group 4 trimethylhydrazido complexes. Inorganica Chimica Acta, 2003, 345, 327-332.	2.4	12
34	Atmospheric Pressure Chemical Vapor Deposition of Gallium Nitride Thin Films. Materials Research Society Symposia Proceedings, 1990, 204, 95.	0.1	11
35	Syntheses and x-ray crystal structures of tetrakis(diphenylamido)niobium(IV) and niobium(IV) amido-halide complexes. Polyhedron, 1993, 12, 2899-2900.	2.2	9
36	Plasma enhanced chemical vapor deposition of silicon nitride films from a metal-organic precursor. Journal of Materials Research, 1994, 9, 3019-3021.	2.6	9

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37	Synthesis and Structures of Zirconium Amideâ^'Iodide Complexes. Inorganic Chemistry, 2002, 41, 4063-4067.	4.0	9
38	Low Temperature Preparation of Gallium Nitride Thin Films. Materials Research Society Symposia Proceedings, 1992, 242, 445.	0.1	7
39	Synthese und Struktur eines resonanzstabilisierten (Trimethylphosphonio)metallapropenids. Angewandte Chemie, 1988, 100, 585-587.	2.0	6
40	[Ni(PtBu)₆] und [Ni(SiH₂)₆] sind isolobal, verwandt mit [In{Mn(CO)₄}₅]^{2â^'} und haben jeweils 16 Valenzelektronen. Angewandte Chemie, 1993, 105, 1682-1684.	2.0	5
41	Synthesis of (Hydrazonido)aluminum Complexes. European Journal of Inorganic Chemistry, 2008, 2008, 5251-5256.	2.0	4
42	Plasma Enhanced Metal-Organic Chemical Vapor Deposition of Germanium Nitride Thin Films. Materials Research Society Symposia Proceedings, 1993, 335, 3.	0.1	1
43	Plasma Enhanced Chemical Vapor Deposition of Zirconium Nitride Thin Films. Materials Research Society Symposia Proceedings, 1995, 410, 289.	0.1	1
44	Low Temperature Atmospheric Pressure Chemical Vapor Deposition of Group 14 Oxide Films. Materials Research Society Symposia Proceedings, 1994, 343, 523.	0.1	0
45	Synthesis of Ferroelectric Strontium Bismuth Tantalate Films from Metal Alkoxide Precursors. Materials Research Society Symposia Proceedings, 1996, 453, 513.	0.1	0